

Title (en)
CURABLE COMPOSITIONS HAVING LESS VOLATILIZATION

Title (de)
HÄRTBARE ZUSAMMENSETZUNGEN MIT VERMINDERTER AUSGASUNG

Title (fr)
COMPOSITIONS DURCISSABLES À DÉGAGEMENT GAZEUX RÉDUIT

Publication
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Application
EP 08865653 A 20081219

Priority

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Abstract (en)

[origin: EP2072550A1] Hardenable composition (I) comprises (a) at least a polyisocyanate; (b) at least an aldehyde or ketone blocked amine; and (c) at least a hydrazide of a carboxylic acid or sulfonic acid having a melting point of at least 100[deg] C, preferably at least 150[deg] C; where the amount of (b) is 0.3-1.1 equivalent of hydrazide group/equivalent of aldehyde or keto group, by which the amine group is blocked. Independent claims are included for: (1) a process for adhering a substrate S1 with a substrate S2 comprising either applying (I) on a substrate (S1) at less than 40[deg] C, contacting the applied substrate (S1) with the substrate (S2) within the open time of (I) and hardening the applied composition at less than 40[deg] C, or applying (I) on the substrates (S1) and (S2) at less than 40[deg] C, contacting the applied composition together within the open time of the composition, and hardening the composition at less than 40[deg] C; (2) a process for sealing the substrates (S1) and (S2), comprising applying (I) between the substrates (S1) and (S2), such that (I) is contacted with (S1) and (S2), at less than 40[deg] C, and hardening the applied composition at less than 40[deg] C, where the substrates (S1) and (S2) are different; (3) a process for coating the substrate (S1), comprising applying (I) on the substrate (S1) at less than 40[deg] C within the open time, and hardening the applied composition at less than 40[deg] C; (4) a hardened composition obtained by hardening (I) at less than 40[deg] C using water, e.g. in the form of water vapor, and subsequently warming at ≥ 80 [deg] C, where the hardened composition comprises at least an amide compound of formula (W 1>-(C(=O)-NH-N=C(Q 1>)(Q 2>)) p) (d1), ((Q 1>)(Q 2>)C=N-NH-(C(=O)) m-C(=O)-NH-N=C(Q 1>)(Q 2>)) (d2) or (X-(S(=O) 2-NH-N=C(Q 1>)(Q 2>)) q) (d3); and (5) an aldazide compound (e) of formula (W 1>-(C(=O)-NH-N=CH-C(R 1>)(R 2>)-Z 1>) p1) (e1) or (Z 1>-C(R 1>)(R 2>)-CH=N-NH-(C(=O)) m-C(=O)-NH-N=CH-C(R 1>)(R 2>)-Z 1>) (e2). W 1>p-valent hydrazide of carboxylic acid with a melting point of at least 100[deg] C, preferably at least 150[deg] C, after removing p-hydrazide group; X : q-valent hydrazide of a sulfonic acid with a melting point of at least 100[deg] C, preferably at least 150[deg] C, after removing q-sulfonic acid hydrazide group; m : 0 or 1; p : 1-4, preferably 2; q : 1-4; Q 1>H, Z 3>, Z 5>or Z 8>; Q 2>Y 1>(when Q 1>is H), Z 4>(when Q 1>is Z 3>), -CH(Z 6>)(Z 7>) (when Q 1>is Z 5>), Z 9>(when Q 1>is Z 8>); Y 1>1-35C-organic residue optionally having heteroatoms, preferably -C(R 1>)(R 2>)(Z 1>) or Z 2>; p1 : 2-4, preferably 2; R 1>, R 2>univalent 1-12C hydrocarbon, preferably CH 3; or R 1>R 2>5-8C, preferably 6C carbocyclic ring, whose one part is optionally substituted by 4-20C bivalent hydrocarbons; Z 1>an univalent 1-32C hydrocarbon optionally having at least a heteroatom, preferably O in the form of ether-, carbonyl- or ester group, or preferably N in form of tertiary amino group; Z 1>an univalent 1-32C hydrocarbon optionally having at least a heteroatom, preferably O in the form of ether-, carbonyl- or ester group, or preferably N in form of tertiary amino group, preferably (-CH(R 3>)-O-R 4>) (a1), (-CH(R 3>)-O-C(=O)-R 5>) (a2) or (-CH(R 3>)-N(R 6>)(R 7>)) (a3); R 3>H, 1-12C-(cyclo)alkyl or 1-12C-arylalkyl; R 4>1-30C, preferably 11-30C hydrocarbon, which optionally contains ether acid atom; R 5>H, 1-30C, preferably 11C-alkyl optionally with cyclic part and optionally contains at least a heteroatom, preferably oxygen in the form of ether-, carbonyl- or ester group, unsaturated 5-30C hydrocarbon or optionally substituted aromatic or heteroaromatic 5- or 6-membered ring; either R 6>, R 7>a univalent 1-20C-aliphatic, 1-20C-cycloaliphatic or 1-20C-arylaliphatic residue, which optionally contains heteroatom in the form of ether oxygen or tertiary amine nitrogen; or R 6>R 7>optionally substituted 5-8, preferably 6 membered ring with heteroatom in the form of ether oxygen or tertiary amine nitrogen, whose one part contains divalent 3-20C-organic residue; Z 2>optionally 5-8, preferably 6 membered optionally substituted (hetero)aryl, or C(=O)-R 8>; R 8>H, alkoxy, optionally substituted at least 6C alkenyl- or arylalkenyl; either Z 3>, Z 4>univalent 1-12C-hydrocarbon; or Z 3>Z 4>5-8C, preferably 6C optionally substituted carbocyclic ring, whose one part contains a bivalent 4-20C-hydrocarbon; either Z 5>, Z 6>H or an univalent 1-12C; or Z 5>Z 6>5-8C, preferably 6C-carbocyclic residue, whose one part contains a bivalent 3-20C hydrocarbon; and Z 7>-Z 9>H or an univalent 1-12C-hydrocarbon.

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